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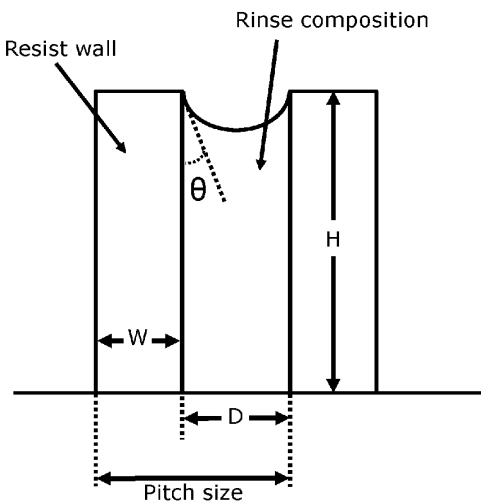


Fig. 1

(57) Abstract: To provide an electronic device manufacturing aqueous solution capable of suppressing defects. To provide an electronic device manufacturing aqueous solution comprising a sulfonic acid derivative (A) having a certain structure, a solvent (B) comprising water and a hydroxy derivative (C) having a certain structure.

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